

IN THE CLAIMS:

1. (Currently amended) A method of reducing the dislocations present in a SiGe heterojunction bipolar transistor, said method comprising the steps of:

(a) providing a semiconductor substrate comprising a collector region and isolation regions adjacent said collector region ~~having isolation regions formed therein, said semiconductor substrate having an upper surface;~~

(b) recessing a portion of the isolation regions below an ~~the~~ upper surface of said collector region in said semiconductor substrate so as to provide a recessed isolation surface; and

(c) forming a SiGe layer on the upper surface of the ~~upper surface of the~~ semiconductor substrate as well as said recessed isolation surface, wherein said recessing controls facet formation at edges ~~of at~~ the SiGe layer and the upper surface of the collector.

2. (Original) The method of Claim 1 wherein said isolation regions are trench isolation regions.

3. (Original) The method of Claim 2 wherein said trench isolation regions are formed by lithography, etching and trench filling.

4. (Original) The method of Claim 3 wherein said trench filling includes deposition of SiO₂.

5. (Original) The method of Claim 1 wherein a patterned dielectric layer is formed on a portion of said isolation regions prior to conducting step (b).

6. (Currently Amended) The method of Claim 5 wherein said patterned dielectric layer is composed of a nitride.

7. (Original) The method of Claim 1 wherein said recessing includes lithography and etching.
8. (Original) The method of Claim 1 wherein after said recessing a patterned dielectric is formed on a portion of the isolation region that is not recessed.
9. (Original) The method of Claim 1 wherein said SiGe layer is formed by a deposition process selected from the group consisting of ultra-high vacuum chemical vapor deposition (UHVCVD), molecular beam epitaxy (MBE), rapid thermal chemical vapor deposition (RTCVD) and plasma-enhanced chemical vapor deposition (PECVD).
10. (Currently amended) The method of Claim 1 further comprising the steps of:
- (d) forming an insulator on said SiGe layer;
 - (e) providing an opening in said insulator so as to expose a portion of said SiGe layer ~~base-region~~;
 - (f) forming an emitter material on said insulator and in said opening so as to contact said SiGe layer ~~base-region~~; and
 - (g) patterning said emitter material and said insulator so as to form a patterned emitter and a patterned insulator on said SiGe layer ~~base-region~~.

Claims 11-19 (Canceled)